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Serial Number: 10500455

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Inventor Information for 10/500455

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US 20050252816 A1	20051117	Process for producing compression bag and compression bag	206/524.8	206/484	Ootsubo, Ryouichi
US 20050196077 A1	20050908	Slider for sealable storage bag and sealable storage bag provided with the slider	383/64	24/400	Ootsubo, Ryouichi et al.
US 6329119 B1	20011211	Negative type resist composition	430/270.1	430/921	Suetsugu; Masumi et al.
US 6156476 A	20001205	Positive photoresist composition	430/270.1	430/326; 430/905; 430/910	Takeyama; Naoki et al.
US 5846688 A	19981208	Photoresist composition	430/270.1	430/920	Fukui; Nobuhito et al.
US 5800966 A	19980901	Positive photoresist composition	430/283.1	430/270.1; 430/281.1; 430/326	Ueda; Yuji et al.
US 5585218 A	19961217	Photoresist composition containing alkyletherified polyvinylphenol	430/270.1	430/325; 430/920; 430/921; 430/924	Nakano; Yuko et al.
US 5420331 A	19950530	Cyclic carbonate compounds, method for producing the same and positive photoresist composition using the same	558/268	430/270.1	Ueda; Yuji et al.
US 5397679 A	19950314	Cyclic carbonate compounds, method for producing the same and positive	430/270.1	430/326; 430/905; 430/909; 430/920; 430/921	Ueda; Yuji et al.

		photoresist composition using the same			
US 5395727 A	19950307	Positive resist composition containing a novolak resin made from an aldehyde and dimer of isopropenyl phenol	430/192	430/165; 430/193; 528/153; 528/155	Uetani; Yasunori et al.
US 5304456 A	19940419	Negative photoresist composition	430/270.1	430/905; 430/914; 430/921; 522/109; 522/111; 522/166; 522/33; 522/63; 525/497; 528/153	Ueda; Yuji et al.
US 5077264 A	19911231	Cyan dye-donor element used in thermal transfer and thermal transfer sheet using it	503/227	428/913; 428/914; 8/471	Hayashi; Yoshiaki et al.
US 4977261 A	19901211	Anthraquinone compound	544/198		Kayane; Yutaka et al.